



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Helmut Wurzer et al. Art Unit : 1763
Serial No. : 09/882,289 Examiner : George A. Goudreau
Filed : June 15, 2001
Title : METHOD FOR FABRICATING A BARRIER LAYER

Commissioner for Patents
Washington, D.C. 20231

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RESPONSE TO RESTRICTION REQUIREMENT

Responsive to the action mailed March 6, 2003, applicant elects the invention of Group I (claims 8 to 15) drawn to a method for making a semiconductor comprised of first oxidizing the Si based substrate followed by second treating the substrate to form an oxygen impervious layer between the oxide layer, and the Si based substrate. The election is made without traverse.

No fee is believed to be due at this time; however, if any fees are due please apply any charges to Deposit Account No. 06-1050 referencing attorney docket number 12816-018001.

Respectfully submitted,

Date: 3/20/03

Faustino A. Lichauco
Reg. No. 41,942

Fish & Richardson P.C.
225 Franklin Street
Boston, Massachusetts 02110-2804
Telephone: (617) 542-5070
Facsimile: (617) 542-8906

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I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

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